

# Nano Devices, Fabrication and Testing

# **Module Information**

2022.01, Approved

# **Summary Information**

Module Code	7532ESIST
Formal Module Title	Nano Devices, Fabrication and Testing
Owning School	Engineering
Career	Postgraduate Taught
Credits	20
Academic level	FHEQ Level 7
Grading Schema	50

#### Teaching Responsibility

LJMU Schools involved in Delivery
LJMU Partner Taught

#### Partner Teaching Institution

Institution Name	
Sri Lanka Technological Campus	

# **Learning Methods**

Learning Method Type	Hours
Lecture	22
Tutorial	22

# Module Offering(s)

Display Name	Location	Start Month	Duration Number Duration Unit
JAN-PAR	PAR	January	12 Weeks

### Aims and Outcomes

Aims

To develop an understanding of the latest development and challenges encountered by the microelectronic industry. To gain knowledge in the fabrication and testing of microelectronic devices. To enhance knowledge in latest consumer electronic products.

#### After completing the module the student should be able to:

#### Learning Outcomes

Code	Number	Description	
MLO1	1	Analyse the performance of latest consumer electronic products	
MLO2	2	Critically appraise MOS fabrication process and techniques	
MLO3	3	Critically evaluate testing techniques and appreciate reliability issues	

### **Module Content**

Outline Syllabus	An overview of the history of microelectronic industry and the milestones in the theory of microelectronic devices. Advanced microelectronic devices and systems: submicrometer MOSFETs, FINFETs, NOR and NAND Flash memories, 3D memories, SRAM and DRAM, SOI transistors and thin film transistors (TFTs), and nano-wire devices.Liquid Crystal Display (LCD) systems and Charge-Coupled Devices (CCDs) cameras. Short-channel effects: charge sharing effects, drain induced barrier lowering and gate induced leakage current.New materials for metals, gate dielectrics, and semiconductors.Fabrications: typical MOS process flow and techniques, wafer cleaning, deposition (CVD and PECVD), masks and lithography, ion implantation, metallization, oxidation, epitaxy, dry etching (plasma and reactive ions), isolation techniques, and device variabilities.Testing and reliabilities: typical procedure and techniques, time-dependent dielectric breakdown (TDDB) and stress-induced-leakage-currents (SILC), Fowler-Nordheim injection, interface states and space charges in the oxide, the high and low frequency differential capacitance-voltage techniques, hot carrier induced degradation, bias temperature instabilities, lifetime prediction.
Module Overview	
Additional Information	This level 7 module extends a prospective student's knowledge of the state-of-the-art electronic devices and systems. The emphasis is on the differences between an advanced device and a traditional one. The fabrication, testing and reliability issues will be addressed.UNESCO Sustainable Development Goals1. Good Health and Wellbeing2. Quality Education3. Decent Work and Economic Growth4. Industry, Innovation and Infrastructure5. Responsible Consumption and Production6. Climate Action7. Partnerships for the Goals

### Assessments

Assignment Category	Assessment Name	Weight	Exam/Test Length (hours)	Module Learning Outcome Mapping
Exam	Exam	100	3	MLO1, MLO2, MLO3

### **Module Contacts**

#### Module Leader

Contact Name	Applies to all offerings	Offerings
Jian Zhang	Yes	N/A

#### Partner Module Team

Contact Name

Applies to all offerings

Offerings